

REMARKS

Claims 1 and 5-13 are pending in this application. By this Amendment, claim 1 is amended to incorporate the subject matter recited in claim 4. Accordingly, claim 4 is canceled. Claim 5 is amended to change its dependency in view of the cancellation of claim 4. Claims 8 and 9 are also amended.

Reconsideration of the application is respectfully requested.

The Office Action applies U.S. Patent 4,289,574 to Radigan ("Radigan"). However, the Office Action does not list Radigan in a Form PTO-892. Accordingly, the Examiner is respectfully requested to list Radigan in a Form PTO-892 in the next Office Action.

The Office Action rejects claims 1 and 6 under 35 U.S.C. §102(b) over Radigan. This rejection is respectfully traversed.

Radigan discloses a device having conductors 34 and 36 that are in contact with each other via a contact hole and an aluminum oxide layer 35. See Fig. 6 and col. 5, lines 13-27. However, Radigan does not disclose or suggest a plurality of one of a first conductive layer and a second conductive layer extending parallel to one another at a predetermined pitch, as recited in claim 1. Therefore, Radigan does not disclose each and every element recited in claim 1, and claim 6 depending therefrom. Accordingly, withdrawal of the rejection of claims 1 and 6 under 35 U.S.C. §102(b) is respectfully requested.

The Office Action rejects claims 1, 4, 5, 7 and 10-13 under 35 U.S.C. §102(b) over U.S. Patent 6,104,040 to Kawachi et al. ("Kawachi"). This rejection is respectfully traversed.

The Office Action asserts that Kawachi discloses all elements recited in claim 1. However, Kawachi does not disclose or suggest an insulating interlayer having a contact hole, as recited in claim 1.

In particular, Kawachi discloses a gap ("contact hole") formed in an n-type a-Si layers 31, 32. However, an n-type a-Si layer is a conductive layer. Thus, the gap is not a contact hole formed in an insulating layer.

Kawachi discloses an insulating (a-Si) layer 30. See Fig. 1 and col. 5, lines 10-20.

However, the insulating layer does not have a contact hole. In particular, the insulating layer 30 only has a depressed portion where a p-type a-Si layer 33 is located. Such a depressed portion does not constitute a "contact hole" this goes through the insulating layer 30.

In view of the above, Kawachi does not disclose an insulating interlayer having a contact hole. Thus, Kawachi does not disclose or suggest each and every element recited in claim 1, and claims 5, 7 and 10-13 depending therefrom. Accordingly, withdrawal of the rejection of claims 1, 5, 7 and 10-13 under 35 U.S.C. §102(b) is respectfully requested.

The Office Action rejects claims 8 and 9 under 35 U.S.C. §103(a) over Radigan in view of U.S. Patent 6,307,216 to Huh et al. ("Huh"). This rejection is respectfully traversed.

The Office Action acknowledges that Radigan does not disclose or suggest a contact hole that is rectangular in plan view, but asserts that Huh discloses such a feature. However, the contact holes C1, C2, C3 and C4 disclosed in Huh are all squares in plan view. See Fig. 1 and col. 4, lines 16-34.

Huh does not suggest contact holes that are rectangular, but not square, in plan view. In particular, the rectangular contact holes provide a longer dimension along a conductive line. Thus, rectangular contact holes that have a longer dimension in one direction (i.e., are not square) ensure more reliable contact with a conductive line. Also, such rectangular contact holes provide reliable contact with conductive layers that extend diagonally with respect to the edges of the rectangular contact holes. See the specification at, for example, paragraph [0011]. Huh does not recognize such advantages of such rectangular contact holes.

In view of the above, Huh does not disclose or suggest contact holes that are rectangular, but not square, in plan view. Therefore, Huh does not supply the subject matter lacking in Radigan.

Additionally, Huh does not disclose or suggest a plurality of one of a first conductive layer and a second conductive layer extending parallel to one another at a predetermined pitch,

as recited in claim 1. Therefore, Huh does not supply this subject matter that is also lacking in Radigan, as discussed above in connection with the rejection of claim 1.

For any or all of the above reasons, Radigan and Huh, either individually or in combination, do not disclose or suggest the subject matter recited in claim 1 and claims 8 and 9 depending therefrom. Accordingly, withdrawal of the rejection of claims 8 and 9 under 35 U.S.C. §103(a) is respectfully requested.

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1 and 5-13 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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Date: April 24, 2006

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